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UNITED STATES OF AMERICA

An electro-modulating device Titre de l'invention Title of the invention. Bezeichnung der Erfindung

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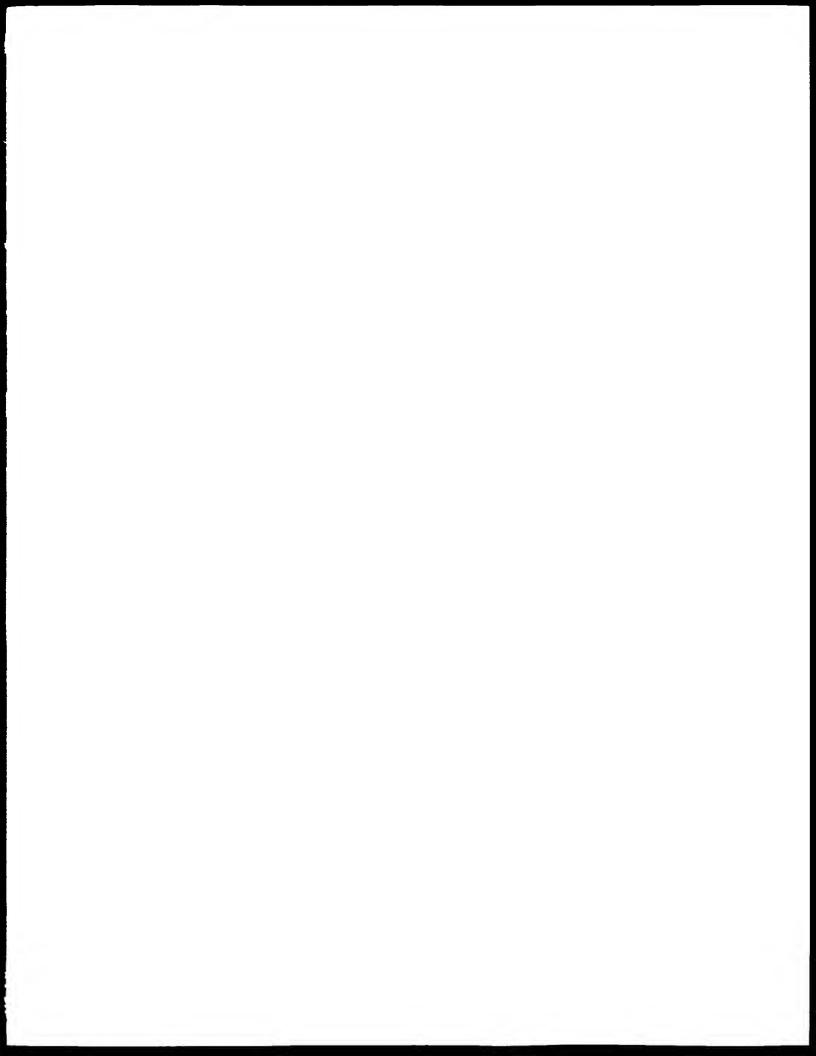
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An Electro-modulating Device

The present invention relates to an electro-modulating device for use as part of an opto-electronic communication network.

In an opto-electronic communication network, it can be desirable to modulate light by passing the light through a modulator. Normally the modulator is formed from a modulator material whose optical properties depend on the electric field applied across it, so that modulating the electric field across the modulator material results in a modulation in the intensity and/or phase of light passing 15 through it.

It is known to modulate light with a modulator having a light input and a light output. One optic fibre is coupled to the modulator input so that light of constant intensity can be passed into the modulator output so that modulated light is coupled to the modulator can be received. This requires two fibres to be coupled to the modulator.

25 It is an object of the present invention to address the above issues.

According to the present invention, there is provided an electro-modulating device comprising a modulating element, or the modulating element having a modulating medium for

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modulating light passing therethrough, an optical inputto modulation of the light and exits the medium after
modulation of the light, a light reflector, and electrodes
for applying an electric field across the modulating

medium, wherein:

the input-output surface, the medium and the reflector are arranged so that light enters the medium through the to travel input-output surface, travels through the medium towards back through the medium towards the input-output surface, and exits the medium through the input-output surface,

input-output surface and the reflector; and input-output surface and the reflector; and

the refractive index of the medium is responsive to the of the light exiting the input-output surface is dependent on the applied electric field.

It will be appreciated that the light may be visible but 25 may alternatively be invisible electromagnetic radiation, such as infra red radiation.

The term refractive index is intended to include the real part and/or the imaginary part thereof, such that a change in the refractive index of the modulating medium can

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result in a change in the phase and/or intensity of light

Only a single optic fibre needs to be coupled to the serves as both an input and an output.

Because the electric field is transverse to the direction of light traversing the modulating medium, it will be likely to position the electrodes such that they are less likely to cause an obstruction to the entry and exit of light into and out of the modulating medium.

electro-modulating device to a achieve a given degree of 20 reducing the voltage that needs to be applied to modulation achieved with the electro-modulating device, or thereby increasing the тре magnitude reflector, gug әұз sarīace ingut-output optical регмееи modulating medium will be approximately twice the distance 91 The effective path length of light travelling through the

Preferably, the modulating element will be formed from a section of semiconductor wafer and the modulating medium 25 will be formed from an active layer on or in the semiconductor wafer, the active layer having a plurality of edges and the input-output surface residing on an edge of the active layer. If an optic fibre having an end portion is used to feed light into and out of the modulating medium, the end portion of the fibre can

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conveniently be positioned close to the input-output surface, in line with and parallel to the active layer forming the modulating medium, thereby making it easier to connect the electro-modulating device to the optic fibre.

If the modulating element is formed from a semiconductor wafer, the modulating medium may be an active layer situated between a first layer of conducting semiconductor, the first and second layers of conducting semiconductor forming the active layer, normal to the active layer. Since the sctive layer, normal to semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to conducting layers of semiconductor can be very close to

The modulating element may be a mesa with side walls etched on the semiconductor wafer, such that the edges and/or ends of the active layer lie on the side walls of the mesa may be buried, or the modulating element may be formed by a ridge structure.

electric field applied across the modulating medium will

Alternatively, the edge of the active layer may reside on cleaved side walls formed by cleaving the wafer.

The electro-modulating device will preferably include a mounting surface on which there is mounted the modulating element. The mounting surface will preferably have a element. The mounting surface will preferably have a clamp, housing, adhesive area or other securing means for

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be increased.

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for receiving the end portion of an optic fibre. by a silicon substrate having a V-groove etched thereon preferred embodiment, the mounting surface will be formed modulating medium through the input-output surface. In a fibre can be coupled into and out of the from the securing the end portion of an optic fibre such that light

- 5 -

continuous layer of semiconductor. breferably MITT apınb ILOM lormed эq surface are integrally formed, the modulating medium and substrate. If the modulating element and the mounting mounting surface, which will preferably be a semiconductor The modulating element may be integrally formed with the for quiding light into and out of the modulating element. The mounting surface may have a light guide formed thereon

silicon oxides and/or nitrides in which case the light The substrate may be formed from layers of silicon and

guide may be defined on the substrate by etching.

reflector need not be entirely reflective and may allow layer and the reflector. It will be appreciated that the the active layer or there may be a gap between the active modulator element. The reflector may be in contact with mounted on the mounting surface, facing an end wall of the modulator element, or alternatively the reflector may be wall of reflective material deposited on an end The reflector may be formed by at least one layer of

some transmission therethrough.

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The reflector may be a distributed bragg reflector having a plurality of layers, or the reflector may be a layer of layer of insulator may be provided between the metal layer and the end wall of the modulator element to reduce the risk of the electrodes on the modulator element being short circuited by the metal layer.

quantum well layer. 20 electric field. The modulating layer may have a multiple real part of the refractive index changes with applied modulating medium will be a material where at least the device is intended to modulate the phase of the light, the the applied electric field. SI the electro-modulating JΙ De a material whose absorption coefficient is dependent on intensity of light, the modulating medium will preferably electro-modulating device is intended to modulate the a semiconductor containing In, Ga, As, and P or Al. If the material, preferably semiconductor such as GaAs or InP, or OI The modulating medium will preferably be an electro-optic

In a preferred embodiment, the modulating element is formed from a semiconductor wafer wherein the modulating medium is formed from a multiple quantum well layer of conducting Inp. The modulating medium may be doped with one polarity of doping and the electrodes may be doped with in opposite polarity of doping in order to form a p-n junction between each electrode and the modulating medium.

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The modulating element may be formed from a polymeric material, and may be coupled with a waveguide also formed from a polymeric material.

reference to the following drawings in which:

Figure 1 shows a schematic side view of an electro-modulating device according to the invention;

Figure 2 shows a plan view of the electro-modulating device of Figure 1;

Figure 3 shows a view of a portion of the electron modulating device of Figure 1 looking in the direction

marked A;

Eigure 4 shows a schematic plan view of a

Figure 5 shows a cross sectional view through the

Figure 6 shows a cross sectional view along the line

SS I-I of Figure 4; and,

Figure 7 shows a cross sectional view through an electro-modulating device with a buried middle layer.

30 In Figure 1, there is shown a schematic side view, not to

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26 together form a reflector 28. SI of metal 26. The dielectric layer 24 and the metal layer 24, which in this example is Alumina, followed by a layer end wall 22, there has been deposited a dielectric layer a back end wall 22, both of which are cleaved. On the back InP. The modulating element 14 has a front end wall 20 and 01 layer 16 of InGaAsP, and a lower layer 17 of conducting conducting InP, an active middle multiple quantum well section of semiconductor wafer having an upper layer 15 of device 10 has modulating element 14 formed from a cleaved electro-modulating Тре 10. qevice electro-modulating 12 and into the which travels down the optic fibre at another end of the fibre 12 produces infra red light 11 of an optic fibre 12 mounted thereon. A light source 18 scale, of an electro-modulating device 10 having one end

Light from the optic fibre 12 enters the active middle layer 16 through the front wall 20, the area where the active middle layer 16 intersects the front wall 20 serving as an optical input-output 21. The light travels through the middle layer 16 towards the reflected back towards the front wall 20, where it fibre 12. When travelling through the middle layer 16, the exits the modulator element 14 and returns into the optic fibre 12. When travelling through the middle layer 16, the light is at least partially confined therein by the upper 15 and the modulator element 17, which act as confining layers because of their different refractive index with the respect to the middle layer 16.

30 A radio frequency voltage source 30 is connected to the

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upper layer 20 and the lower layer 22, the upper and lower layer 20,22 acting as electrodes such that a radio frequency voltage signal 32 applied between the upper and lower layers 20,22 results in a corresponding electric field across the middle layer 16. The optical properties of the active middle layer 16 with the result that the electric field applied across it, with the result that the intensity or phase of the light travelling through the middle layer 16 is modulated by the radio frequency voltage source 30. Typically, the radio frequency voltage source will operate at a frequency of 10 GHz or more.

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part of the refractive index of the middle layer. layer will cause a significant change in at least the real the middle small changes in the electric field across modulated, the dc component will be chosen such that 52 JO рразе муєке гує apow phase-modulating of the light. If the electro-modulator is to be used in a absorption edge in the InGaAsP is close to the wavelength component will be chosen such that the wavelength of the mode where the intensity of light is modulated, 20 electro-modulator is to be used in an intensity-modulating position of the absorption edge of this layer. II the to the active middle layer 16 will change the wavelength superposed with an ac component. The dc component applied component gc 9 contains frequency voltage signal 32 SI radio frequency voltage source 30 such that the radio A dc voltage source 34 may be provided in series with the

30 As can be seen from Figures 1 to 3, the modulating element

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14 is mounted on a substrate 40 made from silicon, the modulating element being secured to the substrate with Ausn solder. The substrate has a groove 42 etched therein for receiving the optic fibre. The groove 42 is positioned such that when the end 11 of the optic fibre 12 is located in the groove 42, the fibre end 11 is pointing towards the optical input-output 21 of the modulating element. A clamp optical input-output 21 of the modulating element. A clamp optical input-output 21 of the groove 42.

The distance between the front wall 20 and the back wall 22 of the modulator element is about 300 µm, and the combined thickness of the upper layer 15, the middle layer 15 16 and the lower layer 17 is about 100 µm. The middle layer 15 is about 101 µm. The middle layer 15 is about 101 µm. The middle layer 16 is about 0.5 µm thick.

coming together at a cross junction 55. and a second light guide 52b, the two light guides 52a,52b strips which act respectively as a first light guide 52a 52 layer 16 has been partially removed so as to leave two layer 16. As can be seen from Figure 5, the light guide lower semiconductor 17 layer followed by a light guide formed on a substrate 40 onto which there has been grown a interferometer ЪЧТ integrally formed therewith. 20 interferometer 50 having an electro-modulating device 10 Mach-Zehnder В JO ΛŢĠM plan SMOUS 9 Figure

Towards the end of the first light guide 52a, there is 30 situated the electro-modulating device 10. The electro-

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electric field. applied дүр uo is also dependent device modulation such that the phase of the light exiting the electro-16b is dependent on the electric field applied across it, medium 16b. The refractive index of the modulating medium SI so as to apply an electric field across the modulating electrode 15 and the layer 17 forming the lower electrode, дүр source, is connected **Irequency** CO voltage modulating medium 16b. A voltage source 30, here a radio grea above pre peen removed except чe иŢ OI formed from a conducting layer of semiconductor the modulating medium 16b, the upper electrode 15 being integrally formed. An upper electrode 15 is provided the first light guide 52a and the modulating element 16b is tormed from a portion leb of the light guide layer le, The modulating medium of the electro-modulating device 10 electrode layer 17 that are common with interferometer 50. substrate paving 105 TOMGI gug .6 *tuferferometer* ΟÞ integrally гре MITH lormed SŢ 0 T device modulating

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travelling down the first light guide 52a meets with the 28b. At the cross junction 55 where the reflected light junction 55 and is reflected back by the second reflector SSB anṛqe ттдрг zecoug дус errers 8 I reflector 28, Another part of the light from the light ду reflected back towards the light source by 52 guide 52a enters the electro-modulating device 10 and is from a light source l8 travelling down the first light modulating medium 16b, such that one part of the light A first reflector 28a is positioned at the end of the

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fibre and used as an output. the performance of the system or may be coupled to optic device 10. This Light may conveniently be used to monitor detector 19 will be modulated by the electro-modulating amplitude of light from the cross junction 55 reaching a Hence the modulating medium 16b. applied across 52b, the light amplitude will depend on the electric field reflected light travelling down the second light

to conbjeq шау ре electro-modulating device interferometer, and that the light guide 52a extending 10 shown in Figure 5 need not be integrally formed with an It will be appreciated that the electro-modulating device

another opto-electronic device.

is provided below the strip 16 for applying a modulation 15 is provided above the strip 16 and a lower electrode 17 a region of a second semiconductor 21. An upper electrode the form of a strip 16 of a first semiconductor buried in electro-modulating device 10 having a modulating medium in In Figure 7, there is shown a cross sectional view of an

voltage to the strip 16.

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Claims:

electro-modulating device An (10)comprising 5 modulating element (14), the modulating element (14)having a modulating medium (16) for modulating light passing therethrough, an optical input-output surface (21) by which light both enters the medium (16) modulation of the light and exits the medium (16) after 10 modulation of the light, a light reflector (28), electrodes (15,17) for applying an electric field across the modulating medium (16), wherein:

the input-output surface (21), the medium (16) and the reflector (28) are arranged so that light enters the medium through the input-output surface (21), travels through the medium (16) towards the reflector (28), is reflected by the reflector (28) to travel back through the medium (16) towards the input-output surface (21), and exits the medium through the input-output surface (21);

the electric field is transverse to the direction of propagation of light traversing the medium (16) between the input-output surface and the reflector (28); and

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the refractive index of the medium (16) is responsive to the applied electric field so that the intensity and/or phase of the light exiting the input-output surface (21) is dependent on the applied electric field.

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- 2. An electro-modulating device (10) as claimed in Claim 1, wherein the modulating element (14) is formed from a section of semiconductor wafer (40,15,16,17) and the modulating medium (16) is formed from an active layer (16) on or in the semiconductor wafer, the active layer (16) having a plurality of edges (20,22) and the input-output surface (21) residing on an edge (20) of the active layer.
- 3. An electro-modulating device (10) as claimed in Claim 2, wherein the modulating medium (16) is an active layer situated between a first layer of conducting semiconductor (15) and a second layer (17) of conducting semiconductor, the first and second layers of conducting semiconductor forming the electrodes (15,17) for applying a bias across the modulating medium (16).
 - 4. An electro-modulating device (10) as claimed in Claim 2 or Claim 3, wherein the electro-modulating device (10) has a mounting surface (41) on which there is mounted the modulating element (14).
- 5. An electro-modulating device (10) as claimed in Claim 4, wherein the mounting surface (41) has securing means (43) for securing the end portion (11) of an optic fibre (12) such that light from the fibre (12) can be coupled into and out of the modulating medium (16) through the input-output surface (21).
- 6. An electro-modulating device (10) as claimed in Claim 30 5, wherein the mounting surface (41) is formed from a

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silicon substrate having a V-groove (42) etched thereon for receiving the end portion (11) of an optic fibre (12).

- 7. An electro-modulating device (10) as claimed in any one of Claims 4 to 6, wherein the mounting surface has a light guide (52a,52b) formed thereon for guiding light into and out of the modulating element (14).
- 8. An electro-modulating device (10) as claimed in Claim 10 7, wherein the light guide (52a) and modulating medium (16b) are formed from a continuous layer of semiconductor (16).
- 9. An electro-modulating device (10) as claimed in any previous claim wherein the modulating element (14) has at least one end wall (22) and the reflector (28) is formed by at least one layer of reflective material (26) deposited on the end wall (22) of the modulator element.
- 20 10. An electro-modulating device (10) as claimed in any of Claims 2 to 9, wherein the modulating medium (16) is formed from a layer of InGaAsP, and each electrode is formed from a layer of conducting InP.

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Abstract

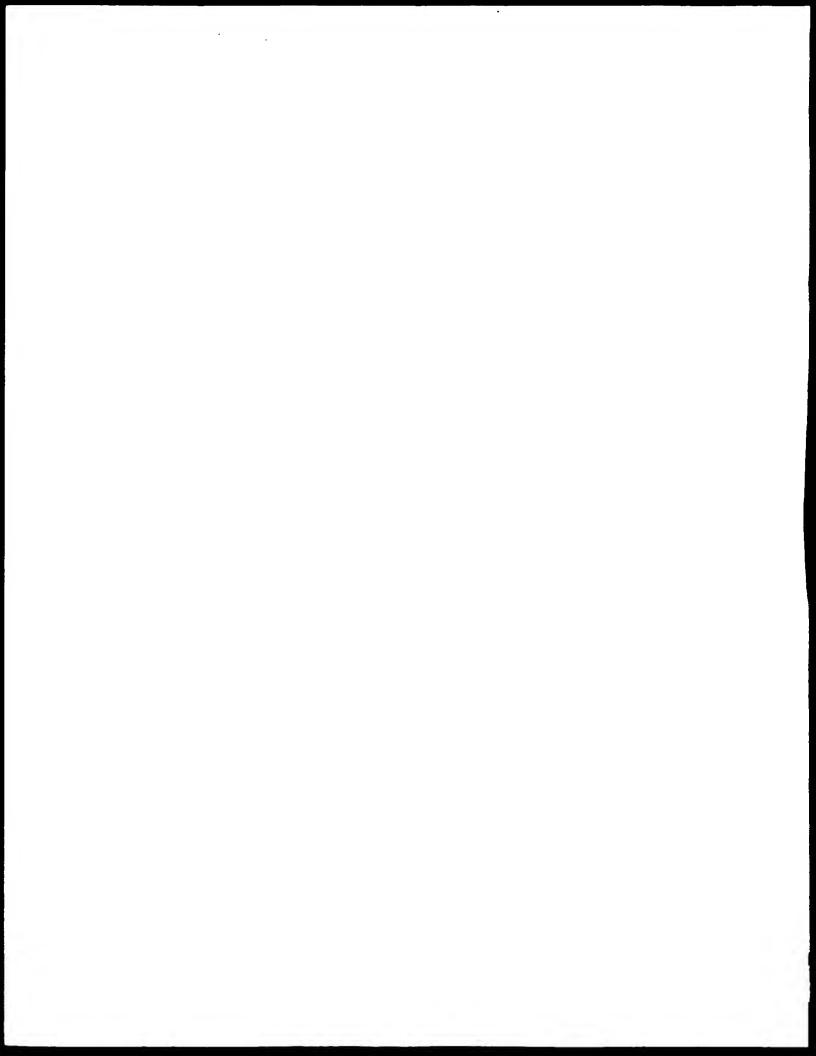
An Electro-modulating Device

5 This relates to an electro-modulating device (10) modulating light from a light source, as part of an optoelectronic communication network. The electro-modulating device (10) has a modulating medium (16) for modulating light passing therethrough by varying an electric field applied across the modulating medium (16), an optical 10 input-output surface (21), a light reflector (28), and electrodes (15,17) for applying the varying electric field the modulating medium (16). The input-output surface (21), the medium (16) and the reflector (28) are arranged so that light enters the medium (16) through the 15 input-output surface (21), travels through the medium (16) towards the reflector (28), is reflected by the reflector (28) to travel back through the medium (16) towards the input-output surface (21), and exits the medium through the input-output surface (21). The electric field 20 is transverse to light traversing the medium (16) between the input-out surface and the reflector (28), to make it easier to couple an optic fibre to the input-output surface (21) of the modulating medium (16).

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Figure 1



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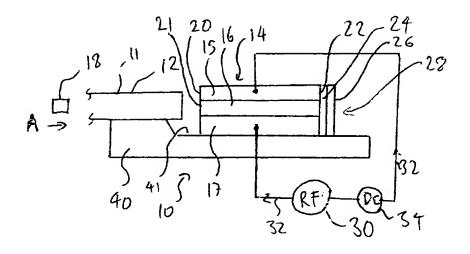
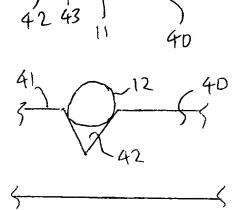




Fig. 2

Fig. 1



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Fig. 3

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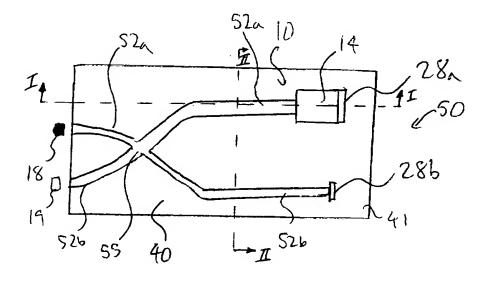


Fig. 4

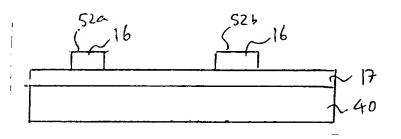


Fig. 5

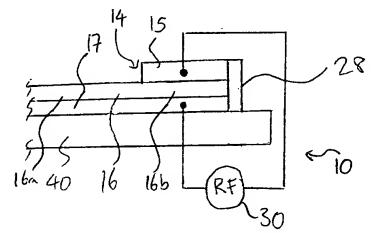


Fig. 6

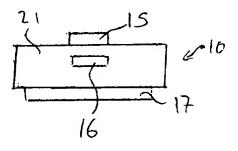


Fig. 7